BE- VII - R2012/CBSGS-B10-VLSIC-15/12/16-11-2

QP Code: 812902

		(3 Hours) [Total Marks	: 80
-	N.	 I. B.: (1) Question No. 1 is compulsory. (2) Solve any three from remaining five questions. (3) Draw neat labelled diagram wherever necessary. (4) For layouts, use Graph paper. (5) Assumptions should be clearly stated. 	
1.	(b)	Explain CVD process in VLSI fabrication.	~ 20 e
2.	(a) (b)	With block diagrams,	10 10
3.	(a) (b)	Find the threshold voltage of NMOS transistor having the substrate doping density $N_A = 10^{15}/\text{cm}^3$, the poly-gate doping density $N_D = 10^{20}/\text{cm}^3$, the gate oxide layer thickness $t_{ox} = 600 \text{ A}^\circ$, the fixed oxide charge $N_{ox} = 2 \times 10^{10}/\text{cm}^2$, the substrate bias voltage $V_{SB} = 2V$. Find V_T . With neat diagram, explain n-well process of CMOS fabrication.	10 10
4.	(a) (b)	behavioral style modelling. (ii) Write VHDL code for 1 bit full subtractor circuit. (i) Explain voltage-current relationship of n-MOS transistor under various operating condition.	5 5 5
		(ii) Explain short channel effect in MOSFET.	5
5.	(a)	Derive relations of V _{IL} , V _{IH} , V _{OH} , V _{OL} for depletion load NMOS inverter in terms of device parameters.	10
	(b)	Draw circuit diagram and stick diagram for the given expression F = AB + AD, (i) Using NMOS depletion load inverter circuit (ii) Using CMOS inverter	10
6.	(a)	Draw λ based layout for 2 input NAND gate with depletion MOSFET as load with aspect ratio for the driver is 2:1 and load is 4:1.	10
	(d)		10